

attraction electrode. The conductor pattern includes a power supplying terminal formed on the second portion of the first insulating layer. The terminal member includes a contact part which is in contact with the power supplying terminal. The urging unit urges the contact part of the terminal member to the power supplying terminal of the electrostatic chuck. The wiring line is electrically connected to the terminal member. In an embodiment, the wiring line may be electrically connected to the terminal member through the urging unit. The power supply is electrically connected to the wiring line.

[005a] Accordingly, in one aspect of the disclosure, there is provided an electrostatic attraction apparatus comprising: an electrostatic chuck configured to attract and hold a processing target object, the electrostatic chuck including: a base including a first face and a second face different from the first face, a first insulating layer formed on the base and including a first portion extending on the first face and a second portion extending on at least a portion of the second face, an attraction electrode formed on the first portion, a second insulating layer formed on the first portion and the attraction electrode, and a conductor pattern formed on the first insulating layer and electrically connected to the attraction electrode, the conductor pattern including a power supplying terminal formed on the second portion; a terminal member including a contact part contacted to the power supplying terminal; an urging unit configured to urge the contact part of the terminal member to the power supplying terminal and the base; a wiring line electrically connected to the terminal member; and a power supply electrically connected to the wiring line.

[005b] ~~In yet another aspect, there is provided an electrostatic attraction chuck for attracting and holding a processing target object, the chuck comprising: a base including a first face and a second face different from the first face; a first insulating layer formed on the base and~~

WHAT IS CLAIMED IS:

1. An electrostatic attraction apparatus comprising:
 - an electrostatic chuck configured to attract and hold a processing target object, the electrostatic chuck including:
 - a base including a first face and a second face different from the first face,
 - a first insulating layer formed on the base and including a first portion extending on the first face and a second portion extending on at least a portion of the second face,
 - an attraction electrode formed on the first portion,
 - a second insulating layer formed on the first portion and the attraction electrode, and
 - a conductor pattern formed on the first insulating layer and electrically connected to the attraction electrode, the conductor pattern including a power supplying terminal formed on the second portion;
 - a terminal member including a contact part contacted to the power supplying terminal;
 - an urging unit configured to urge the contact part of the terminal member to the power supplying terminal and the base;
 - a wiring line electrically connected to the terminal member; and
 - a power supply electrically connected to the wiring line.

2. The electrostatic attraction apparatus of claim 1, wherein the urging unit is a screw, and

the apparatus further comprises an insulating support member configured to support the screw.

3. The electrostatic attraction apparatus of claim 1, wherein the contact part includes a conductive spring.

4. The electrostatic attraction apparatus of claim 1, wherein the wiring line is electrically connected to the terminal member through the urging unit.

5. The electrostatic attraction apparatus of claim 1, wherein the second face includes a region extending in a direction which is non-parallel to the first face, and the power supplying terminal is formed on the region of the second face through the second portion.

6. The electrostatic attraction apparatus of claim 1, wherein the processing target object is attracted and held at a temperature ranging from -263°C to -60°C .

~~7. An electrostatic attraction chuck for attracting and holding a processing target object, the chuck comprising:~~

~~a base including a first face and a second face different from the first face;~~

~~a first insulating layer formed on the base and including a first portion extending on the first face and a second portion extending on at least a portion of the second face;~~

~~an attraction electrode formed on the first portion;~~

~~a second insulating layer formed on the first portion and the attraction~~

electrode; and

~~a conductor pattern formed on the first insulating layer and electrically connected to the attraction electrode, the conductor pattern including a power supplying terminal formed on the second portion.~~

87. A cooling treatment apparatus comprising:

a processing container;

the electrostatic attraction apparatus defined in claim 1, the electrostatic chuck being provided within the processing container; and

a refrigerator configured to cool the electrostatic chuck.